

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: *Gabric, et al.* Docket No.: INF 2006 VJ 33543 US
Serial No.: 10/586,788 Art Unit: TBD
Filed: July 21, 2006 Examiner: TBD
I.A. Filing Date: January 22, 2005 I.A. No.: PCT/DE2005/000088
For: Plasma Excited Chemical Vapor Deposition Method
Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Dear Sir:

Prior to examination on the merits, Applicant respectfully submits this Preliminary Amendment and remarks as set forth hereinafter.